

UNITED STATES PATENT AND TRADEMARK OFFICE  
**CERTIFICATE OF CORRECTION**

PATENT NO. : 6,825,914 B2  
DATED : November 30, 2004  
INVENTOR(S) : Joachim Schroeder et al.

Page 1 of 1

It is certified that error appears in the above-identified patent and that said Letters Patent is hereby corrected as shown below:

Column 1,

Line 37, replace "contamination and to clean a mixture or an inert gas and" with -- contamination and to clean a mixture of an inert gas and --.

Column 2,

Line 27, replace "By means or an appropriate adaptation or mixing ratio, it" with -- By means of an appropriate adaptation or mixing ratio, it --.

Line 64, replace "also possible in which case the composition must then, or" with -- also possible in which case the composition must then, of --.

Line 65, replace "course, be changed appropriately order to produce overall a" with -- course, be changed appropriately in order to produce overall a --.

Column 3,

Line 25, replace "1) Replacement of air at 243.4 nm by a nitrogen-helium" with

-- 1) Replacement of air at 248.4 nm by a nitrogen-helium --.

Line 27, replace "the mixing ratio is calculated as 1.360% helium with" with

-- the mixing ratio is calculated as 1.36% helium with --.

Line 31, replace "after F. Kohlrausch, Praktische Physik, [Practical Physics]," with

-- after F. Kohlrausch, Praktische Physik, [Practical Physics], --.

Column 4,

Line 44, replace "FIG. 2 is a schematic of a protection exposure machine" with

-- FIG. 2 is a schematic of a projection exposure machine --.

Line 48, replace "principle, see, For example, DE 100 02 26 A1, this design" with

-- principle, see, for example, DE 100 02 26 A1, this design --.

Signed and Sealed this

Twenty-third Day of August, 2005



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JON W. DUDAS  
*Director of the United States Patent and Trademark Office*